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(54) **ORGANIC LIGHT EMITTING DIODE
DISPLAY DEVICE**

(56) **References Cited**

U.S. PATENT DOCUMENTS

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- 6,911,772 B2* 6/2005 Cok H01L 27/3211
313/113
- 8,174,179 B2* 5/2012 Suh H01L 27/322
313/110
- 2004/0217694 A1* 11/2004 Cok G09G 3/3216
313/504
- 2005/0186330 A1* 8/2005 Kim H01L 51/0017
427/66
- 2006/0152150 A1* 7/2006 Boerner C09K 11/0883
313/506
- 2008/0284324 A1* 11/2008 Chun H01L 27/3211
313/504
- 2008/0296600 A1 12/2008 Kwack et al.
- 2011/0121271 A1 5/2011 Jeon et al.
- 2011/0240970 A1* 10/2011 Park H01L 27/3211
257/40

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(Continued)

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FOREIGN PATENT DOCUMENTS

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KR 10-2008-0105308 12/2008
KR 10-2010-0053254 5/2010

(Continued)

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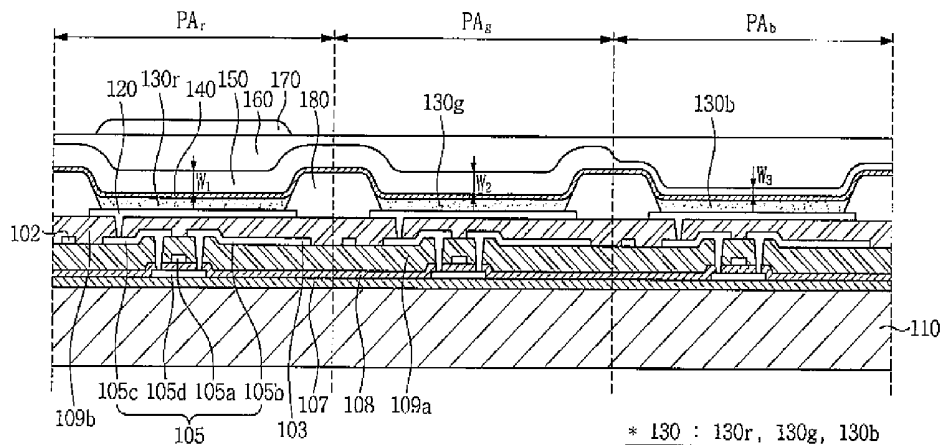
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(2013.01); **H01L 51/5275** (2013.01)

(58) **Field of Classification Search**
None
See application file for complete search history.

(57) **ABSTRACT**

An organic light emitting diode (OLED) display device includes: a first substrate comprising red, green, and blue pixel areas; a first electrode on the first substrate; red, green, and blue organic light emitting layers on the first electrode at the red, green, and blue pixel areas, respectively; a second electrode on the red, green, and blue organic light emitting layers; a capping layer on the second electrode, and having a greater thickness at the red and green pixel areas than a thickness at the blue pixel area; a thin film encapsulation layer on the capping layer; and a red color filter on the thin film encapsulation layer at the red pixel area.

15 Claims, 7 Drawing Sheets



(56)

References Cited

U.S. PATENT DOCUMENTS

2012/0119239 A1 5/2012 Kim et al.
2012/0319145 A1* 12/2012 Weaver H01L 27/3211
257/89
2013/0001532 A1* 1/2013 Hwang H01L 51/0058
257/40
2014/0131674 A1* 5/2014 Park H01L 27/3209
257/40
2014/0284566 A1* 9/2014 Yoo H01L 51/5012
257/40
2014/0291627 A1* 10/2014 Kim H01L 51/0013
257/40
2015/0001480 A1* 1/2015 Kim H01L 51/5265
257/40

FOREIGN PATENT DOCUMENTS

KR 10-2011-0058126 6/2011
KR 10-2012-0053340 5/2012

* cited by examiner

FIG. 1

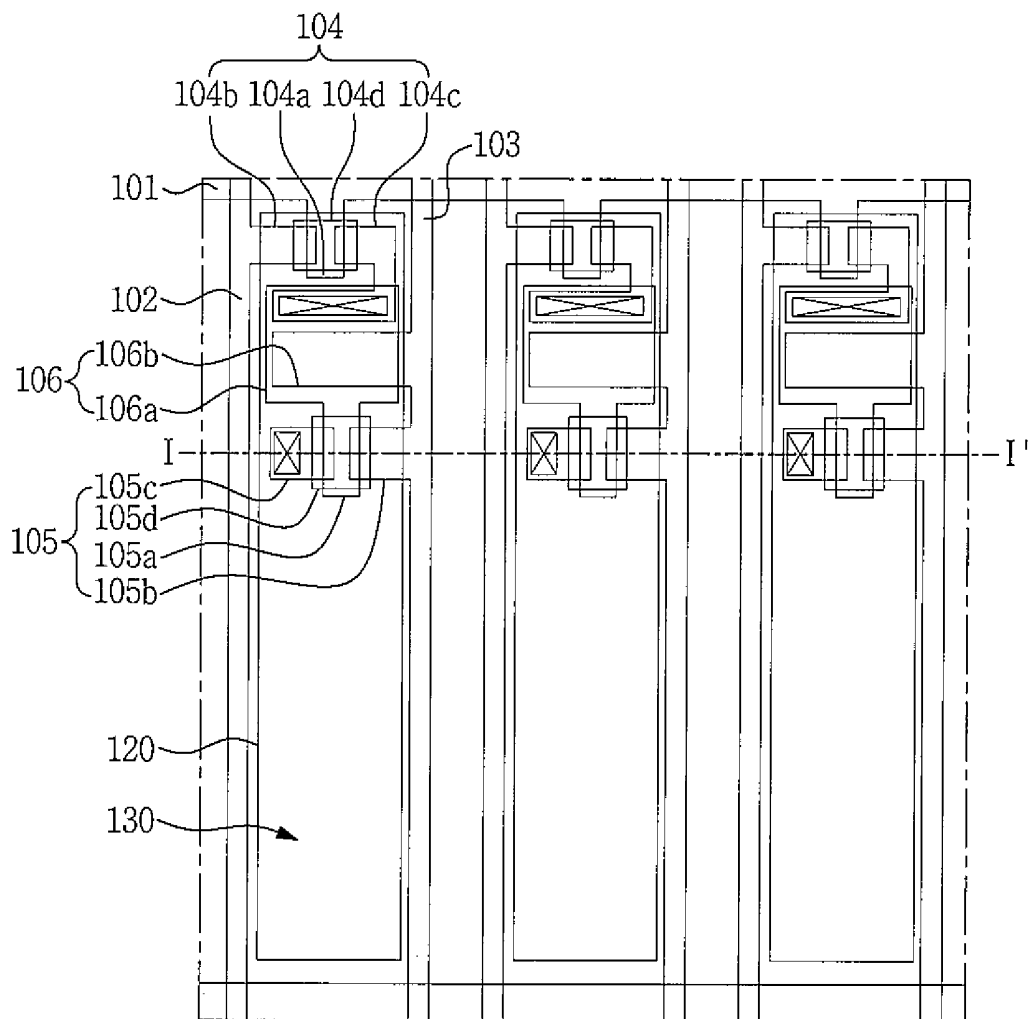


FIG. 2

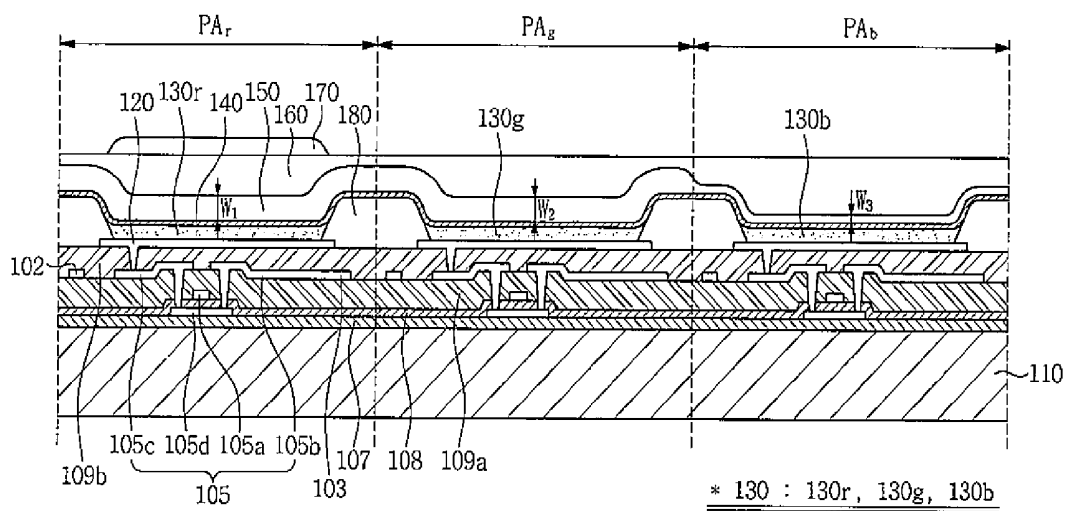


FIG. 3

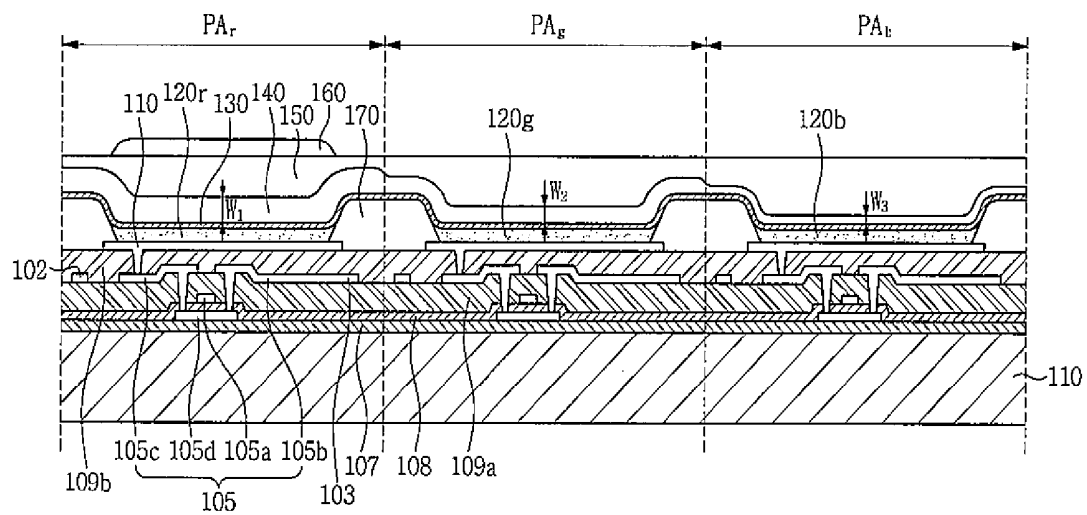


FIG. 4

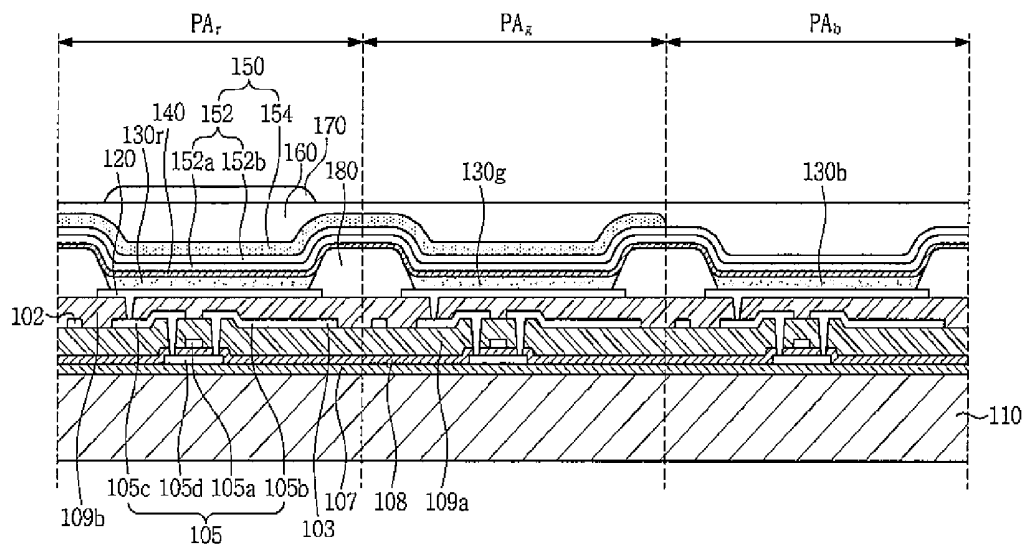


FIG. 5

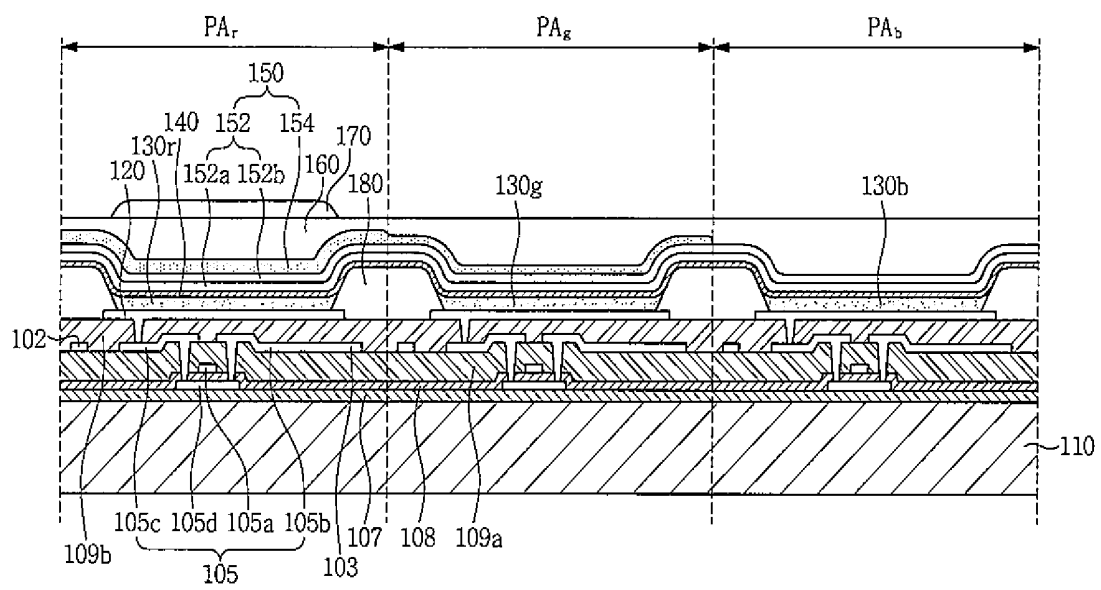


FIG. 6

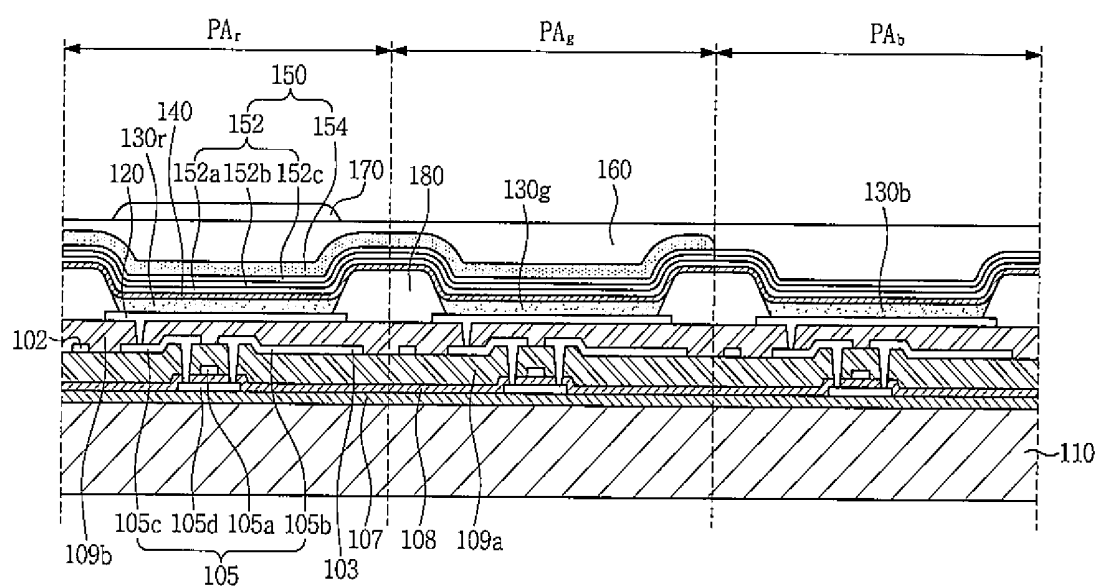
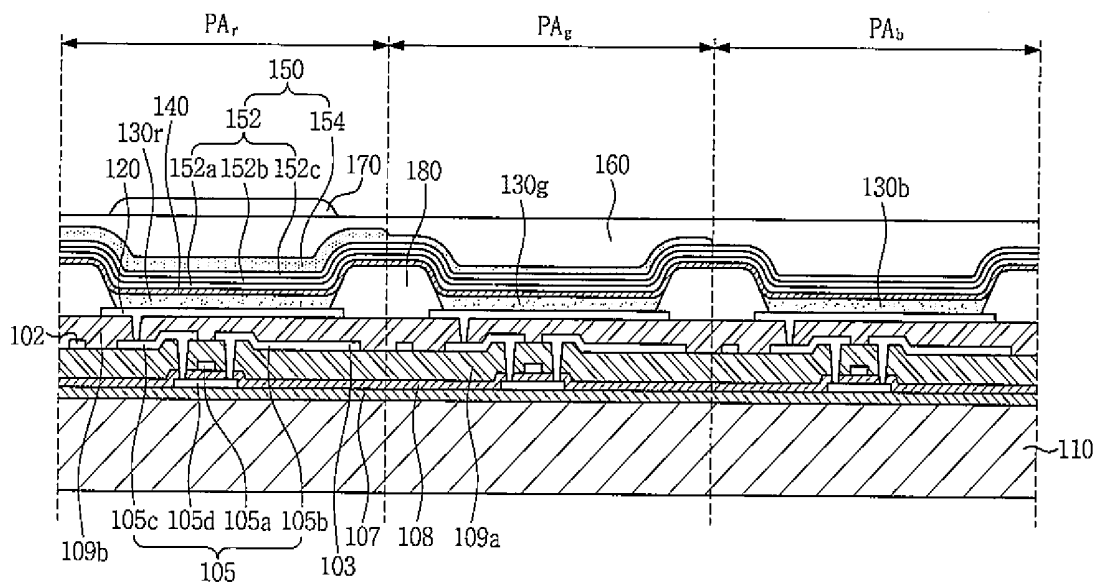


FIG. 7



ORGANIC LIGHT EMITTING DIODE DISPLAY DEVICE

CROSS-REFERENCE TO RELATED APPLICATION

This application claims priority to and the benefit of Korean Patent Application No. 10-2015-0022474, filed on Feb. 13, 2015, in the Korean Intellectual Property Office, the disclosure of which is incorporated herein in its entirety by reference.

BACKGROUND

1. Field

Aspects of embodiments of the present invention relate to an organic light emitting diode (OLED) display device.

2. Description of the Related Art

An organic light emitting diode (OLED) display device is a self-emission-type display device displaying an image using an OLED element which emits light. Such an OLED display device may not require an additional light source, in a manner dissimilar to that of a liquid crystal display (LCD) device, and thus may have a relatively reduced thickness and weight. Further, an OLED display device has characteristics such as relatively low power consumption, relatively high luminance, and relatively high speed of response, thus gaining attention as a next generation display device.

In general, an OLED element includes a hole injection electrode, an organic light emitting layer, and an electron injection electrode. A hole injected from the hole injection electrode and an electron injected from the electron injection electrode are combined with one another within the organic light emitting layer to form an exciton. The OLED element emits light by energy generated when the exciton falls from an excited state to a ground state.

It is to be understood that this background of the technology section is intended to provide useful background for understanding the technology and as such disclosed herein, the technology background section may include ideas, concepts or recognitions that do not constitute prior art.

SUMMARY

Aspects of embodiments of the present invention relate to an organic light emitting diode (OLED) display device, and an OLED display device enhanced in the light efficiency thereof and significantly reduced in a color distortion phenomenon that occurs based on a viewing angle.

Embodiments of the present invention are directed to an organic light emitting diode (OLED) display device having relatively enhanced light efficiency, and significantly reduced color distortion based on a viewing angle.

According to an embodiment of the present invention, an OLED display device includes: a first substrate including red, green, and blue pixel areas; a first electrode on the first substrate; red, green, and blue organic light emitting layers on the first electrode at the red, green, and blue pixel areas, respectively; a second electrode on the red, green, and blue organic light emitting layers; a capping layer on the second electrode, and having a greater thickness at the red and green pixel areas than a thickness at the blue pixel area; a thin film encapsulation layer on the capping layer; and a red color filter on the thin film encapsulation layer at the red pixel area.

The capping layer may have a same thickness in the red and green pixel areas.

The capping layer may have a thickness in a range of 30 nanometers (nm) to 150 nm at the red and green pixel areas, and a thickness in a range of 20 nm to 60 nm at the blue pixel area:

5 The capping layer may have a refractive index in a range of 1.8 to 3.0.

The capping layer may have a greater thickness at the red pixel area than a thickness at the green pixel area.

10 The capping layer may have a thickness in a range of 40 nm to 150 nm at the red pixel area, a thickness in a range of 30 nm to 140 nm at the green pixel area, and a thickness in a range of 20 nm to 60 nm at the blue pixel area.

The capping layer may have a refractive index in a range of 1.8 to 3.0.

15 The capping layer may include a first refractive-index layer comprising at least a first low-refractive-index layer and at least a first high-refractive-index layer at the red, green, and blue pixel areas, and a second refractive-index layer on the first refractive-index layer at the red and green pixel areas.

The first low-refractive-index layer and the first high-refractive-index layer may be arranged sequentially.

The second refractive-index layer may be on the first low-refractive-index layer.

25 The second refractive-index layer may be on the first high-refractive-index layer.

The first low-refractive-index layer may have a refractive index in a range of 1.2 to 1.8, and the first high-refractive-index layer and the second refractive-index layer may have a refractive index in a range of 1.8 to 3.0.

30 The first low-refractive-index layer may have a thickness in a range of 10 nm to 30 nm, the first high-refractive-index layer may have a thickness in a range of 10 nm to 50 nm, and the second refractive-index layer may have a thickness in a range of 5 nm to 80 nm.

The second refractive-index layer may have a same thickness at the red and green pixel areas.

40 The second refractive-index layer may have a greater thickness at the red pixel area than a thickness at the green pixel area.

The foregoing is illustrative only and is not intended to be in any way limiting. In addition to the illustrative aspects, embodiments, and features described above, further aspects, embodiments, and features will become apparent by reference to the drawings and the following detailed description.

BRIEF DESCRIPTION OF THE DRAWINGS

The above and other features and aspects of the present invention of invention will be more clearly understood from the following detailed description taken in conjunction with the accompanying drawings, in which:

FIG. 1 is a plan view illustrating an organic light emitting diode (OLED) display device according to the present invention;

FIG. 2 is a cross-sectional view taken along line I-I' of FIG. 1 according to a first example embodiment of the present invention;

60 FIG. 3 is a cross-sectional view taken along line I-I' of FIG. 1 according to a second example embodiment of the present invention;

FIG. 4 is a cross-sectional view taken along line I-I' of FIG. 1 according to a third example embodiment of the present invention;

65 FIG. 5 is a cross-sectional view taken along line I-I' of FIG. 1 according to a fourth example embodiment of the present invention;

FIG. 6 is a cross-sectional view taken along line I-I' of FIG. 1 according to a fifth example embodiment of the present invention; and

FIG. 7 is a cross-sectional view taken along line I-I' of FIG. 1 according to a sixth example embodiment of the present invention.

DETAILED DESCRIPTION

Aspects and features of the present invention and methods for achieving them will be made clear from example embodiments described below in more detail with reference to the accompanying drawings. The present invention may, however, be embodied in many different forms and should not be construed as being limited to the example embodiments set forth herein. Rather, these example embodiments are provided so that this disclosure will be more thorough and more complete, and will more fully convey the scope of the invention to those skilled in the art. The present invention is merely defined by the scope of the claims. Therefore, well-known constituent elements, operations and techniques may not be described in detail in the example embodiments in order to prevent the present invention from being obscurely interpreted. Like reference numerals refer to like elements throughout the specification.

The spatially relative terms “below”, “beneath”, “lower”, “above”, “upper”, and the like, may be used herein for ease of description to describe the relationship between one element or component and another element or component as illustrated in the drawings. It will be understood that the spatially relative terms are intended to encompass different orientations of the device in use or operation, in addition to the orientation depicted in the drawings. For example, in the case where a device shown in the drawing is turned over, the device positioned “below” or “beneath” another device may be placed “above” another device. Accordingly, the illustrative term “below” may include both the lower and upper positions. The device may also be oriented in the other direction, and thus the spatially relative terms may be interpreted differently depending on the orientations.

All terminologies used herein are merely used to describe embodiments of the inventive concept and may be modified according to the relevant art and the intention of an applicant. Therefore, the terms used herein should be interpreted as having a meaning that is consistent with their meanings in the context of the present disclosure, and is not intended to limit the invention. As used herein, the singular forms “a,” “an,” and “the” are intended to include the plural forms as well, unless the context clearly indicates otherwise. It will be further understood that the terms “comprises,” “comprising,” “includes” and/or “including,” when used in this specification, specify the presence of stated features, integers, steps, operations, elements, and/or components, but do not preclude the presence or addition of one or more other features, integers, steps, operations, elements, components, and/or groups thereof.

Unless otherwise defined, all terms used herein (including technical and scientific terms) have the same meaning as commonly understood by those skilled in the art to which this invention pertains. It will be further understood that terms, such as those defined in commonly used dictionaries, should be interpreted as having a meaning that is consistent with their meaning in the context of the relevant art and will not be interpreted in an idealized or overly formal sense unless expressly so defined herein.

FIG. 1 is a plan view illustrating an organic light emitting diode (OLED) display device according to some embodi-

ments of the present invention; and FIG. 2 is a cross-sectional view taken along the line I-I' of FIG. 1 according to a some example embodiments of the present invention.

Referring to FIGS. 1 and 2, an OLED display device according to the present invention may include a gate line 101, a data line 102 insulated from and intersecting the gate line 101, a common power line 103, a switching thin film transistor (TFT) 104, a driving TFT 105, and a capacitor (CAP) 106.

In other words, a single pixel of the OLED display device according to the present invention may have a 2TFT-1 CAP structure including two thin film transistors, for example, the switching TFT 104 and the driving TFT 105, and a single capacitor, for example, the CAP 106. However, the structure of the pixel of the OLED display device is not limited thereto, and three or more thin film transistors and two or more capacitors may be included in a single pixel.

The switching TFT 104 may select a pixel to perform light emission. The switching TFT 104 may include a switching gate electrode 104a connected to the gate line 101, a switching source electrode 104b connected to the data line 102, a switching drain electrode 104c connected to a first capacitor plate 106a, and a switching semiconductor layer 104d.

The driving TFT 105 may apply driving power for allowing an organic light emitting layer 130 in the pixel selected by the switching TFT 104 to perform light emission. The driving TFT 105 may include a driving gate electrode 105a connected to the first capacitor plate 106a, a driving source electrode 105b connected to the common power line 103, a driving drain electrode 105c connected to the first electrode 110, and a driving semiconductor layer 105d.

The CAP 106 may include the first capacitor plate 106a and a second capacitor plate 106b. The first capacitor plate 106a may be connected to the switching drain electrode 104c and the driving gate electrode 105a, and the second capacitor plate 106b may be connected to the common power line 103. Capacitance of the CAP 106 may be determined by electric charges stored in the CAP 106 and voltages between the first capacitor plate 106a and the second capacitor plate 106b.

A voltage having a level equivalent to a difference between a level of a data voltage transmitted by (or from) the switching TFT 104 and a level of a common voltage applied from the common power line 103 to the driving TFT 105 may be stored in the CAP 106, and a current having a level equivalent to the level of the voltage stored in the CAP 106 may flow to the organic light emitting layer 130 through the driving TFT 105 to allow the organic light emitting layer 130 to perform light emission.

The first substrate 110 may use (or include) an insulating substrate formed of any suitable insulating substrate materials such as glass, quartz, ceramic, plastic, and the like. However, the material forming the first substrate 110 is not limited thereto. Accordingly, the first substrate 110 may also use (or include) a metallic substrate material, for example, stainless steel, or the like.

The first substrate 110 may include red, green, and blue pixel areas PA_r, PA_g, and PA_b. The red, green, and blue pixel areas PA_r, PA_g, and PA_b may be defined by a pixel defining layer 180, which is to be described further below, and may be arranged or formed on the first substrate 110.

A buffer layer 107 may be arranged or formed on the first substrate 110. The buffer layer 107 may prevent or efficiently reduce the infiltration of undesired components or external contaminants such as moisture or impure elements through the first substrate 110 and may also planarize a surface of the

first substrate **110**. The buffer layer **107** may be formed of one of an inorganic insulating layer and an organic insulating layer. For example, the buffer layer **107** may be deposited on the first substrate **110** through various types of deposition processes such as a plasma enhanced chemical vapor deposition (PECVD) process, an atmospheric pressure CVD (APCVD) process, or a low pressure CVD (LPCVD) process, in which SiO_2 , SiN_x , or the like, are used. However, the deposition of the buffer layer **107** is not limited thereto, and according to some embodiments, the buffer layer **107** may be omitted.

The driving semiconductor layer **105d** may be arranged or formed on the buffer layer **107**, and may include a source region, a drain region, and a channel region between the source region and the drain region.

A gate insulating layer **108** may be arranged or formed on the buffer layer **107** to cover the driving semiconductor layer **105d**, and may prevent or efficiently reduce the infiltration of undesired components or external contaminants such as moisture or impure elements through the first substrate **110**. The gate insulating layer **108** may be formed of an insulating material, and may have a monolayer or multilayer structure formed of silicon nitride (SiN_x) or silicon oxide (SiO_x). However, the material forming the gate insulating layer **108** is not limited thereto, and the gate insulating layer **108** may be formed of various insulating materials.

The driving gate electrode **105a** may be arranged or formed on the gate insulating layer **108**, and an insulating interlayer **109a** may be arranged or formed on the gate insulating layer **108** to cover the driving gate electrode **105a**.

The driving source electrode **105b** and the driving drain electrode **105c** may be arranged or formed on the insulating interlayer **109a** to be spaced apart from one another, and may contact the source region and the drain region of the driving semiconductor layer **105d** through respective apertures, each of the apertures being formed in the gate insulating layer **108** and the insulating interlayer **109a**.

A protection layer **109b** may be arranged or formed on the insulating interlayer **109a** to cover the driving source electrode **105b** and the driving drain electrode **105c**. The protection layer **109b** may protect the driving TFT **105**, and may be formed of an inorganic insulating layer and an organic insulating layer.

The first electrode **120**, the organic light emitting layer **130**, and the second electrode **140** may be sequentially arranged or positioned on the protection layer **109b**. The first electrode **120** may be an anode that injects holes and the second electrode **140** may be a cathode that injects electrons. However, the configuration of the first and second electrodes **120** and **140** is not limited thereto, and the first electrode **120** may be a cathode and the second electrode **140** may be an anode.

The organic light emitting layer **130** may include red, green, and blue organic light emitting layers **130r**, **130g**, and **130b**. The red, green, and blue organic light emitting layers **130r**, **130g**, and **130b** may be arranged or formed in the red, green, and blue pixel areas PA_r , PA_g , and PA_b , respectively. The organic light emitting layer **130** may include a low molecular weight organic material or a polymer organic material.

At least one of a hole injection layer and a hole transporting layer may further be interposed between the first electrode **120** and the organic light emitting layer **130**, and at least one of an electron transporting layer and an electron injection layer may further be interposed between the organic light emitting layer **130** and the second electrode **140**.

The OLED display device according to some example embodiments may be a top-emission-type display device. Accordingly, the first electrode **120** may include a reflective layer and the second electrode **140** may include a transmissive layer. However, the type of the OLED display device according to some example embodiments is not limited thereto, and the OLED display device according to some example embodiments may be modified into a bottom-emission-type display device. In this case, the first electrode **120** may include a transmissive layer and the second electrode **140** may include a reflective layer.

The reflective layer and the transmissive layer may include one or more metals of magnesium (Mg), silver (Ag), gold (Au), calcium (Ca), lithium (Li), chromium (Cr), and aluminum (Al) or a metal alloy thereof. The type of the layer, that is, whether the reflective layer or the transmissive layer, may be determined based on the thickness of the layer. In general, the transmissive layer has a thickness of less than or equal to about 200 nanometers (nm).

The first electrode **120** may further include a transparent conductive layer, and the transparent conductive layer may include transparent conductive oxide (TCO) such as indium tin oxide (ITO), indium zinc oxide (IZO), zinc oxide (ZnO), or indium oxide (In_2O_3).

The first electrode **120** may have a structure including a reflective layer, a double-layer structure including a reflective layer and a transparent conductive layer, or a triple-layer structure in which a transparent conductive layer, a reflective layer, and a transparent conductive layer are sequentially stacked. However, the structure of the first electrode **120** is not limited thereto, and the first electrode **120** may have a structure including a transparent conductive layer.

The second electrode **140** may have a structure including a transparent conductive layer. In the case of including a transparent conductive layer, the second electrode **140** may be an anode that injects holes and the first electrode **120** may include a reflective layer to serve as a cathode.

The pixel defining layer **180** may be arranged or formed on the first electrode **120** to cover an edge portion of the first electrode **120** and may have a predetermined aperture through which a center portion of the first electrode **120** is exposed. In other words, the first electrode **120**, the organic light emitting layer **130**, and the second electrode **140** may be sequentially stacked within the aperture of the pixel defining layer **180**. Further, the organic light emitting layer **130** and the second electrode **140** may be formed on the pixel defining layer **180**.

A capping layer **150** may be arranged or formed on the second electrode **140**. The capping layer **150** may protect the first electrode **120**, the organic light emitting layer **130**, and the second electrode **140**, and may assist in efficient dissipation of light generated in the organic light emitting layer **130**, externally of the OLED display device.

The capping layer **150** may have a greater thickness in the red and green pixel areas PA_r and PA_g than that in the blue pixel area PA_b .

For example, the capping layer **150** may have a first thickness W_1 in the red pixel area PA_r , a second thickness W_2 in the green pixel area PA_g , and a third thickness W_3 in the blue pixel area PA_b .

In this instance, the first thickness W_1 and the second thickness W_2 may be the same as one another, and the first thickness W_1 and the second thickness W_2 may be greater than the third thickness W_3 . For the enhanced light extraction efficiency of the OLED display device, the first thickness W_1 and the second thickness W_2 may be in a range of

about 30 nm to about 150 nm, and the third thickness W_3 may be in a range of about 20 nm to about 60 nm.

The capping layer **150** may have a refractive index in a range of about 1.8 to about 2.5, and may be formed of at least one of an inorganic material and an organic material. Accordingly, the capping layer **150** may be formed of one of an inorganic layer and an organic layer, or may be formed of an organic layer containing inorganic particles.

Such inorganic materials applicable to the capping layer **150** may include, for example, zinc oxide, titanium oxide, zirconium oxide, niobium oxide, tantalum oxide, tin oxide, nickel oxide, silicon nitride, indium nitride, and gallium nitride.

Such organic materials applicable to the capping layer **150** may include, for example, poly (3,4-ethylenedioxythiophene) (PEDOT), 4,4'-bis [N-(3-methylphenyl)-N-phenyl amino]biphenyl (TPD), 4,4',4"-tris[(3-methylphenyl)phenyl amino]triphenylamine (m-MTDA), 1,3,5-tris[N,N-bis(2-methylphenyl)-amino]-benzene (o-MTDAB), 1,3,5-tris[N,N-bis(3-methylphenyl)-amino]-benzene (m-MTDAB), 1,3,5-tris[N,N-bis(4-methylphenyl)-amino]-benzene (p-MTDAB), 4,4'-bis[N,N-bis(3-methylphenyl)-amino]-diphenylmethane (BPPM), 4,4'-dicarbazolyl-1,1'-biphenyl (CBP), 4,4',4"-tris(N-carbazole)triphenylamine (TCTA), 2,2',2"-(1,3,5-benzenetolyl)tris-[1-phenyl-1H-benzimidazol] (TPBI), and 3-(4-biphenyl)-4-phenyl-5-t-butylphenyl-1,2,4-triazole (TAZ).

A thin film encapsulation layer **160** may be arranged or formed on the capping layer **150**, and may encapsulate and protect the first electrode **120**, the organic light emitting layer **130**, the second electrode **140**, and the capping layer **150** from the infiltration of external moisture or oxygen thereinto.

The thin film encapsulation layer **160** may have a structure in which at least an organic layer and at least an inorganic layer are alternately stacked. However, the structure of the thin film encapsulation layer **160** is not limited thereto, and the thin film encapsulation layer **160** may have a monolayer structure including one of an inorganic layer and an organic layer.

A red color filter **170** may be arranged or formed on the thin film encapsulation layer **160** in the red pixel area PA_r , and may include a red material or an organic material in which red materials are dispersed.

The OLED display device according to some example embodiments may enhance the light extraction efficiency thereof by including the capping layer **150**, having a greater thickness in the red and green pixel areas PA_r and PA_g than that in the blue pixel area PA_b . However, there may arise an issue of a color distortion phenomenon that occurs based on a viewing angle, more particularly, a phenomenon in which a reddish color is displayed. In this regard, the OLED display device according to some example embodiments may include the red color filter **170** in the red pixel area PA_r , thereby enhancing the light extraction efficiency thereof and significantly reducing the color distortion phenomenon occurring based on a viewing angle.

FIG. 3 is a cross-sectional view taken along line of FIG. 1 according to another example embodiment of the present invention. Referring to FIG. 3, since the OLED display device of FIG. 3 according to some example embodiments has the same configuration as that of the OLED display device of FIG. 2, aside from a capping layer **150**, and some repetitive description thereof may be omitted for conciseness.

The capping layer **150** may have a greater thickness in a red pixel area PA_r than that in green and blue pixel areas PA_g

and PA_b , and may have a greater thickness in the green pixel area PA_g than that in the blue pixel area PA_b .

For example, the capping layer **150** may have a first thickness W_1 in the red pixel area PA_r , a second thickness W_2 in the green pixel area PA_g , and a third thickness W_3 in the blue pixel area PA_b .

In this instance, the first thickness W_1 may be greater than the second thickness W_2 and the third thickness W_3 , and the second thickness W_2 may be greater than the third thickness W_3 . For the enhanced light extraction efficiency of the OLED display device, the first thickness W_1 may be in a range of about 40 nm to about 150 nm, the second thickness W_2 may be in a range of about 30 nm to about 140 nm, and the third thickness W_3 may be in a range of about 20 nm to about 60 nm.

The capping layer **150** may have a refractive index in a range of about 1.8 to about 2.5. Because the capping layer **150** is formed of the same material as that of the capping layer **150** of FIG. 1, some repetitive description thereof may be omitted for conciseness.

FIG. 4 is a cross-sectional view taken along line I-I' of FIG. 1 according to another example embodiment of the present invention. Referring to FIG. 4, because the OLED display device of FIG. 4 has the same configuration as that of the OLED display device of FIG. 2, aside from a capping layer **150**, some repetitive description thereof may be omitted for conciseness.

The capping layer **150** may include a first refractive-index layer **152** arranged or positioned in red, green, and blue pixel areas PA_r , PA_g , and PA_b , and a second refractive-index layer **154** arranged or positioned in the red and green pixel areas PA_r and PA_g .

The first refractive-index layer **152** may include a first low-refractive-index layer **152a** and a first high-refractive-index layer **152b**. The first low-refractive-index layer **152a**, the first high-refractive-index layer **152b**, and the second refractive-index layer **154** may be sequentially arranged or positioned on a second electrode **140**.

The first refractive-index layer **152** may have the same thickness in the red, green, and blue pixel areas PA_r , PA_g , and PA_b , and the second refractive-index layer **154** may have the same thickness in the red and green pixel areas PA_r and PA_g . In this instance, the first low-refractive-index layer **152a** may have a thickness in a range of about 10 nm to about 30 nm, the first high-refractive-index layer **152b** may have a thickness in a range of about 10 nm to about 50 nm, and the second refractive-index layer **154** may have a thickness in a range of about 5 nm to about 80 nm.

The first low-refractive-index layer **152a** may have a refractive index in a range of about 1.2 to about 1.8. The first low-refractive-index layer **152a** may be formed of at least one of an inorganic material and an organic material. Accordingly, the first low-refractive-index layer **152a** may include one of an inorganic layer and an organic layer, or may include an organic layer containing inorganic particles.

Such inorganic materials applicable to the first low-refractive-index layer **152a** may include, for example, silicon oxide and magnesium fluoride.

Such organic materials applicable to the first low-refractive-index layer **152a** may include, for example, acrylic, polyimide, polyamide, and Alq_3 [Tris(8-hydroxyquinolino) aluminum].

The first high-refractive-index layer **152b** and the second refractive-index layer **154** may have a refractive index in a range of about 1.8 to about 3.0. Because the first high-refractive-index layer **152b** and the second refractive-index layer **154** are formed of the same material as that of the

capping layer **150** of FIG. **1**, some repetitive description thereof may be omitted for conciseness.

FIG. **5** is a cross-sectional view taken along line I-I' of FIG. **1** according to another example embodiment of the present invention. Referring to FIG. **5**, because the OLED display device of FIG. **5** may have the same configuration as that of the OLED display device of FIG. **4**, aside from a second refractive-index layer **154**, some repetitive description thereof may be omitted for conciseness.

The second refractive-index layer **154** may have a greater thickness in a red pixel area PA_r , than that in a green pixel area PA_g . In this instance, the second refractive-index layer **154** may have a thickness in a range of about 5 nm to about 80 nm.

The second refractive-index layer **154** may have a refractive index in a range of about 1.8 to about 2.5. Because the second refractive-index layer **154** is formed of the same material as that of the capping layer **150** of FIG. **1**, some repetitive description thereof may be omitted for conciseness.

FIG. **6** is a cross-sectional view taken along the line I-I' of FIG. **1** according to some example embodiments of the present invention. Referring to FIG. **6**, because the OLED display device of FIG. **6** may have the same configuration as that of the OLED display device of FIG. **4**, aside from a first refractive-index layer **152**, some repetitive description thereof may be omitted for conciseness.

The first refractive-index layer **152** may include a first low-refractive-index layer **152a**, a first high-refractive-index layer **152b**, and a second low-refractive-index layer **152c**. The first low-refractive-index layer **152a**, the first high-refractive-index layer **152b**, the second low-refractive-index layer **152c**, and a second refractive-index layer **154** may be sequentially arranged or positioned on a second electrode **140**.

The first refractive-index layer **152** may have the same thickness in red, green, and blue pixel areas PA_r , PA_g , and PA_b . In this instance, the first low-refractive-index layer **152a** and the second low-refractive-index layer **152c** may have a thickness in a range of about 10 nm to about 30 nm, and the first high-refractive-index layer **152b** may have a thickness in a range of about 10 nm to about 50 nm.

FIG. **7** is a cross-sectional view taken along the line I-I' of FIG. **1** according to another example embodiment of the present invention. Referring to FIG. **7**, because the OLED display device of FIG. **7** may have the same configuration as that of the OLED display device of FIG. **5**, aside from a first refractive-index layer **152**, some repetitive description thereof may be omitted for conciseness.

The first refractive-index layer **152** may include a first low-refractive-index layer **152a**, a first high-refractive-index layer **152b**, and a second low-refractive-index layer **152c**. The first low-refractive-index layer **152a**, the first high-refractive-index layer **152b**, the second low-refractive-index layer **152c**, and a second refractive-index layer **154** may be sequentially arranged or positioned on a second electrode **140**.

The first refractive-index layer **152** may have the same thickness in red, green, and blue pixel areas PA_r , PA_g , and PA_b . In this instance, the first low-refractive-index layer **152a** and the second low-refractive-index layer **152c** may have a thickness in a range of about 10 nm to about 30 nm, and the first high-refractive-index layer **152b** may have a thickness in a range of about 10 nm to about 50 nm.

As set forth above, according to some example embodiments, the OLED display device may enhance the light

efficiency thereof and may significantly reduce the color distortion phenomenon occurring based on a viewing angle.

From the foregoing, it will be appreciated that various embodiments in accordance with the present disclosure have been described herein for purposes of illustration, and that various modifications may be made without departing from the scope and spirit of the present teachings. Accordingly, the various embodiments disclosed herein are not intended to be limiting of the true scope and spirit of the present teachings. Therefore, it is to be understood that the foregoing is illustrative of various example embodiments and is not to be construed as limited to the specific example embodiments disclosed, and that modifications to the disclosed example embodiments, as well as other example embodiments, are intended to be included within the scope of the appended claims, and their equivalents.

What is claimed is:

1. An organic light emitting diode (OLED) display device comprising:

- a first substrate comprising red, green, and blue pixel areas;
- a first electrode on the first substrate;
- red, green, and blue organic light emitting layers on the first electrode at the red, green, and blue pixel areas, respectively;
- a second electrode on the red, green, and blue organic light emitting layers;
- a capping layer on the second electrode, and having a greater thickness at the red and green pixel areas than a thickness at the blue pixel area;
- a thin film encapsulation layer on the capping layer; and
- a red color filter on the thin film encapsulation layer at the red pixel area.

2. The organic light emitting diode display device of claim **1**, wherein the capping layer has a same thickness in the red and green pixel areas.

3. The organic light emitting diode display device of claim **2**, wherein the capping layer has a thickness in a range of 30 nanometers (nm) to 150 nm at the red and green pixel areas, and a thickness in a range of 20 nm to 60 nm at the blue pixel area.

4. The organic light emitting diode display device of claim **2**, wherein the capping layer has a refractive index in a range of 1.8 to 3.0.

5. The organic light emitting diode display device of claim **1**, wherein the capping layer has a greater thickness at the red pixel area than a thickness at the green pixel area.

6. The organic light emitting diode display device of claim **5**, wherein the capping layer has a thickness in a range of 40 nm to 150 nm at the red pixel area, a thickness in a range of 30 nm to 140 nm at the green pixel area, and a thickness in a range of 20 nm to 60 nm at the blue pixel area.

7. The organic light emitting diode display device of claim **5**, wherein the capping layer has a refractive index in a range of 1.8 to 3.0.

8. The organic light emitting diode display device of claim **1**, wherein the capping layer comprises a first refractive-index layer comprising at least a first low-refractive-index layer and at least a first high-refractive-index layer at the red, green, and blue pixel areas, and a second refractive-index layer on the first refractive-index layer at the red and green pixel areas.

9. The organic light emitting diode display device of claim **8**, wherein the first low-refractive-index layer and the first high-refractive-index layer are arranged sequentially.

10. The organic light emitting diode display device of claim 9, wherein the second refractive-index layer is on the first low-refractive-index layer.

11. The organic light emitting diode display device of claim 9, wherein the second refractive-index layer is on the first high-refractive-index layer. 5

12. The organic light emitting diode display device of claim 8, wherein the first low-refractive-index layer has a refractive index in a range of 1.2 to 1.8, and the first high-refractive-index layer and the second refractive-index layer have a refractive index in a range of 1.8 to 3.0. 10

13. The organic light emitting diode display device of claim 8, wherein the first low-refractive-index layer has a thickness in a range of 10 nm to 30 nm, the first high-refractive-index layer has a thickness in a range of 10 nm to 50 nm, and the second refractive-index layer has a thickness in a range of 5 nm to 80 nm. 15

14. The organic light emitting diode display device of claim 13, wherein the second refractive-index layer has a same thickness at the red and green pixel areas. 20

15. The organic light emitting diode display device of claim 13, wherein the second refractive-index layer has a greater thickness at the red pixel area than a thickness at the green pixel area.

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专利名称(译)	有机发光二极管显示装置		
公开(公告)号	US9548339	公开(公告)日	2017-01-17
申请号	US14/842767	申请日	2015-09-01
[标]申请(专利权)人(译)	三星显示有限公司		
申请(专利权)人(译)	三星DISPLAY CO. , LTD.		
当前申请(专利权)人(译)	三星DISPLAY CO. , LTD.		
[标]发明人	JEONG HEESEONG		
发明人	JEONG, HEESEONG		
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其他公开文献	US20160240589A1		
外部链接	Espacenet USPTO		

摘要(译)

有机发光二极管 (OLED) 显示装置包括：包括红色，绿色和蓝色像素区域的第一基板;在所述第一基板上的第一电极;红色，绿色和蓝色有机发光层，分别位于所述红色，绿色和蓝色像素区域的所述第一电极上;在所述红色，绿色和蓝色有机发光层上的第二电极;覆盖层，在所述第二电极上，并且在所述红色和绿色像素区域处的厚度大于在所述蓝色像素区域处的厚度;在所述覆盖层上的薄膜封装层;以及在红色像素区域的薄膜封装层上的红色滤色器。

